

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of:	)	
	)	Examiner:
Yuichiro Shindo et al.	)	
	)	Group Art Unit:
Application No.:	)	
	)	
Corresponding International Filing No.:	)	
<b>PCT/JP2005/001488</b>	)	
	)	
Filed: Herewith	)	
	)	
For: HIGH-PURITY Ru POWDER,	)	
SPUTTERING TARGET	)	
OBTAINED BY SINTERING THE	)	
SAME, THIN FILM OBTAINED	)	
BY SPUTTERING THE TARGET	)	
AND PROCESS FOR	)	
PRODUCING THE HIGH-PURITY	)	
Ru POWDER	)	

Mail Stop PCT  
 Commissioner for Patents  
 P.O. Box 1450  
 Alexandria, VA 22313-1450

**FIRST PRELIMINARY AMENDMENT**

Sir:

**Before calculating the filing fee**, please amend the above-identified patent application as follows.

**Amendments to the Claims** are reflected in the listing of claims which begins on page two of this paper.

**Remarks** begin on page three of this paper.